

## REMARKS

Claims 10-13 were pending and under consideration, claims 1-9 having been cancelled as elected for examination in parent application Serial No. 09/161,669.

In the Office Action of September 19, 2006, claims 10-13 were rejected as anticipated by Sano et al (USP 5796154) or obvious in view of Sano et al and Akio (USP 5691548).

In response, and without acquiescing in rejections, claims 10-13 have been cancelled and new claims 14-27 have been added. Additionally, the title of the invention has been slightly amended to better refer to the disclosed method. The rejections are traversed.

New claims 10-27 parallel claims 1-14 of granted parent application 09/161,669, which issued as USP 6614479. It is submitted that claims 10-27 are allowable for the same reasons.

In that regard, Sano et al nowhere discloses an in-layer lens formed by plasma CVD. Instead, in Sano et al, the micro-lens is formed by a spin coating method (see Column 7, lines 41-65). The result is that Sano et al requires an inefficient and burdensome two step process for forming both the lens and the coating. In the present invention, because both the lens and the anti-reflection film are formed using plasma CVD process, there is no need to switch between very different processes, with a resultant increase in production.

In view of the foregoing, it is submitted that claims 14-27 are patentable over the cited art and that the application is in condition for allowance.

Respectfully submitted,

Dated: December 19, 2006

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